Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	11	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5) and (control\$4 independent\$3) near5 electrode and mask near5 multi\$2cell	US-PGPUB; USPAT; USOCR	OR	ON	2006/01/31 10:05
S1	4	(("6027630") or ("5190637")).PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/01 16:29
S2	31	("2306082" "3240685" "3697401" "3745105" "3835017" "4043891" "4080267" "4126533" "4155815" "4294669" "4376017" "4404080" "4452684" "4770754" "4921583" "4985116" "5190637" "5209817" "5271822" "5378583" "5478699" "5501784" "5512162" "5605614" "5614075" "5766441").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/09/08 17:03
S3	0	S2 and controllable near5 electrode	US-PGPUB; USPAT; USOCR	OR	ON	2005/09/08 17:05
S4	149	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5) and controllable near5 electrode	US-PGPUB; USPAT; USOCR	OR	ON	2005/09/08 17:05
S5	31	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5) and controllable near5 electrode and mask	US-PGPUB; USPAT; USOCR	OR	ON	2005/09/09 12:00
S6	142	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5) and independent\$3 near5 electrode and mask	US-PGPUB; USPAT; USOCR	OR	ON	2005/09/08 17:36
S7	3	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5) and independent\$3 near5 electrode and mask near5 multi\$2cell	US-PGPUB; USPAT; USOCR	OR	ON	2006/01/31 10:04

S8	23	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5) and mask near5 multi\$2cell	US-PGPUB; USPAT; USOCR	OR	ON	2005/09/08 17:15
S9	35	(electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5) and mask near5 multi\$2cell	US-PGPUB; USPAT; USOCR	OR	ON	2005/09/09 11:59
S10	o	(electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5) and mask near5 multi\$2cell not S9	US-PGPUB; USPAT; USOCR	OR	ON	2005/09/08 17:16
S11	12	(electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5) and mask near5 multi\$2cell not S8	US-PGPUB; USPAT; USOCR	OR	ON	2005/09/08 17:16
S12	157	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5) and ((three near2 dimension\$2) with structure) and mask	US-PGPUB; USPAT; USOCR	OR	ON	2005/11/02 15:19
S13	23	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5) and ((three near2 dimension\$2) with structure) and mask near5 multi\$2cell	US-PGPUB; USPAT; USOCR	OR	ON	2005/09/09 10:13
S14	18	("205"/118,135.ccls.) and (electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5) and ((three near2 dimension\$2) with structure) and mask near5 multi\$2cell	US-PGPUB; USPAT; USOCR	OR	ON	2005/09/09 10:13
S15	51	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5) and controllable near5 electrode and independent\$3 near5 electrode	US-PGPUB; USPAT; USOCR	OR	ON	2005/09/09 12:00
S16	2	("6008102").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/01 16:41

S17	4	(("5395508") or ("6228242")).PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/01 17:25
S18	4	2002\$4"0185311"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/01 17:25
S19	85	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5) and ((three near2 dimension\$2) with structure) and mask and etch	US-PGPUB; USPAT; USOCR	OR	ON	2005/11/02 15:19
S20	132	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5) and ((three near2 dimension\$2) with structure) and mask and etch\$3 and deposit\$3	US-PGPUB; USPAT; USOCR	OR	ON	2005/11/02 15:20
S21	132	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5) and ((three near2 dimension\$2) with structure) and mask and etch\$3 and deposit\$3 and layer	US-PGPUB; USPAT; USOCR	OR	ON	2005/11/02 15:21
S22	96	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5) and ((three near2 dimension\$2) with structure) and mask and etch\$3 and deposit\$3 and (void hole)	US-PGPUB; USPAT; USOCR	OR	ON	2005/11/02 15:40
S23	4	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5) and ((three near2 dimension\$2) with structure) and mask and etch\$3 and deposit\$3 and (void hole) and (independent\$3 controllable) near5 electrode	US-PGPUB; USPAT; USOCR	OR	ON	2005/11/02 15:41